		(1)
	Application No.	Applicant(s)	
Nation of Allowahility	10/616,508	SHIN, HYEON SANG	
Notice of Allowability	Examiner	Art Unit	
· ·	James M. Mitchell	2813	
The MAILING DATE of this communication appearable daims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGOT the Office or upon petition by the applicant. See 37 CFR 1.313	OR REMAINS) CLOSED in this apport of the properties of the communication of the communication is subject to the communication in the communication is subject.	olication. If not include will be mailed in due	ed course. THIS
1. This communication is responsive to <u>3/30/2005</u> .			
2. 🔀 The allowed claim(s) is/are <u>1-3</u> .			
3. $igotimes$ The drawings filed on $\underline{10 July\ 2003}$ are accepted by the Exa	aminer.		
4. Acknowledgment is made of a claim for foreign priority under a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 1. Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of noted below. Failure to timely comply will result in ABANDONMS THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which gives 1. CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftsperson 1. Corrected by the Notice of Draftsperson 1. Corrected by Including Changes required by the attached Examiner's Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying Indicia such as the application number (see 37 CFR 1.8 each sheet. Replacement sheet(s) should be labeled as such in the paper No./Mail Document Properties of the priority documents of the priority documents have the priority documents have a claim for the priority documents have a cl	been received. been received in Application No uments have been received in this in of this communication to file a reply in ENT of this application. Ited. Note the attached EXAMINER's reason(s) why the oath or declarate is be submitted. On's Patent Drawing Review (PTO- Amendment / Comment or in the One of the according to 37 CFR 1.121(content).	complying with the recomplying attached with the first the front (not the fig.)	quirements OTICE OF back) of
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date 5/16/05 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	5. Notice of Informal Page 1 Notice of Informal Page 1 No./Mail Dat Pa	(PTO-413), e nent/Comment ent of Reasons for Allo	·

U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04) TECHNOLOGY CENTER 2800

DETAILED ACTION

This office action is in response to applicant's amendment filed March 30, 2005.

Allowable Subject Matter

Claims 1-3 are allowed.

The following is an examiner's statement of reasons for allowance: the prior art does not disclose or make obvious a method of forming a floating gate where an oxide film in a trench is polished and then etched to form a protrusion in the film having a nipple shape, covering the nipple with a polysilicon, polishing the polysilicon until the protrusion is exposed and then cleaning the protrusion to form the protrusion into a semicircle.

While semicircular shaped protrusions are known in the art as shown for example in Nakamura (U. S. 6,222,225) and Lai (U.S. 2002/0119628) through a polishing and etching step, the prior art fails to shows forming a second layer of polysilicon over the protrusion, using a second polishing step and then a cleaning step (wet etch process) to form the protrusion into the semicircular shape.

Furthermore while utilizing a polishing and a two etch step process is known in the art as shown in Fukazawa et al. (U.S. 6,291,300), besides its failure to show or make obvious use of a second polysilicon, the second etch instead of forming the protrusion into a semicircle, makes the protrusion more planar.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably Art Unit: 2813

accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. The prior art discloses in: Lin (U.S. 6,057,208) forming the protrusion of an isolation film with a polishing, etching; and in Inard (U.S. 6,518,114) forming the protrusion of an isolation film with a polishing, etching and then bombardment step.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to James M. Mitchell whose telephone number is (571) 272-1931. The examiner can normally be reached on M-F 8:00-4:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on (571) 272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Art Unit: 2813

Jmm